Course I	Akashi College		Year	Year 2022		Course Title	Micromachine	
	informat	tion						
Course Coo	de	4041			Course Categor	y Specializ	red / Elective	
Class Format Lecture					Credits	Academ	Credit: 2	
Department Mechanica Engineerii			al and Electronic System ng		Student Grade	Adv. 2nd		
Term		Second S	emester		Classes per Week 2			
Textbook Teaching M								
Instructor		MATSUZI	JKA Naoki					
Course C	Objectiv	es						
(2) Unders (3) Can ex (4) Unders	stand and oplain mic ostand and	can explain romachines can explain	the principles from their stru detection princ	ic materials and ca of typical semicond cture to the fabrical ciples of sensors an chniques. (F) and (I	uctor micromachi tion process. (F) d driving principle	ining technique		
Rubric								
			Ideal Level		Standard Level		Unacceptable Level	
Achievement 1			Fully understand the characteristics of anisotropic material and can accurately calculate the physical property values of crystal orientation.		Understand the characteristics of anisotropic materials and can calculate the physical property values of crystal orientation.		Do not understand the characteristics of anisotropic materials and cannot calculate the physical property values of crystal orientation.	
Achievement 2			Fully understand and can accurately explain the principles		Understand and can explain the principles of typical semiconductor micromachining techniques.		Do not understand and cannot explain the principles of typical semiconductor micromachining techniques.	
Achieveme	Achievement 3			Can explain micromachines in detail from their structure to the fabrication process.		cromachines ture to the ess.	Cannot explain micromachines detail from their structure to the fabrication process.	
			Fully understand and can accurately explain detection		Understand and can explain detection principles of sensors and driving principles of actuators.		Do not understand and cannot explain detection principles of sensors and driving principles of actuators.	
			Can accurately apply sensor and actuator design techniques.		Can apply sensor and actuator design techniques.		Cannot apply sensor and actuator design techniques.	
Assigned	d Depart	tment Ob	jectives					
Teaching	g Metho	d	-					
Outline		sensors, in a wide technique	actuators, and range of fields es and microma	electronic circuits u . The first half of th cchine fabrication m	sing semiconduct is course will exp ethods. The seco	tor micromachi lain typical sem and half will ext	at integrate micro structures, ning technology. They are applied niconductor micromachining plain the principles of sensors used ator design techniques.	
Style				lecture-style forma				
Notice		knowledg Students	of materials, ar ge will be explai who miss 1/3 o	nd electronic circuits ned in class. or more of classes v	s. However, this	course is open	s include the learning time dy / review, and completing ge of engineering materials, to all students as the necessary grade.	
Characte	eristics o	of Class /	Division in L	earning	<u> </u>			
☐ Active I	Learning		☐ Aided by	ICT	☐ Applicable to	Remote Class	☐ Instructor Professionally Experienced	
Course P	Plan							
		-	heme		Goals			
	3rd Quarter	1st	An overview of	micromachines		Understand mid and scaling law	cromachine development history s.	
		2nd I	Physical propert	ies of single-crysta	l silicon (1)		e crystal structure, manufacturing nisotropic properties of single-	
		3rd I	Physical propert	ies of single-crysta	silicon (2)	Understand the calculation method for the physical properties in arbitrary crystal orients of single-crystal silicon.		
۱.		4th I	hotolithography			Understand the principles of photolithography.		
2nd (		5th I	lm deposition (1)			Understand the sputter, vapor deposition, and chemical vapor deposition methods.		
						Understand thermal oxidation and impurity diffusion.		
2nd Semeste		6th I	Film deposition	(2)			ermal oxidation and impurity	
2nd Semeste			Film deposition Etching (1)	(2)		<u>diffusion.</u> Understand ligi	ermal oxidation and impurity  uid-based isotropic and anisotropic e-crystal silicon.	
2nd Semeste		7th I	·	(2)		diffusion. Understand liqu etching of singl	uid-based isotropic and anisotropic	

		10th Sensor design technology (1)			Understand typical micro-sensors and sensing principles.					
		11th	Sensor design ted	Gensor design technology (2)			Understand how to design piezoresistive pressure sensors.			
		12th	Sensor design tec		Design a piezo	Design a piezoresistive pressure sensor.				
	13th Actuator design technology (1)					Understand typical micro actuators and their driving principles.				
			Actuator design to	echnology (2)		Understand ho actuator.	Understand how to design an electrostatic drive actuator.			
		15th	Actuator design to	ctuator design technology (3)			Design a electrostatic drive actuator.			
	16th		Final exam							
Evaluati	on M	ethod and \	Weight (%)							
		Examination	Assignments	Mutual Evaluations between students	Behavior	Portfolio	Other	Total		
Subtotal		60	40	0	0	0	0	100		
Basic Proficiency		0	0	0	0	0	0	0		
Specialized Proficiency		60	40	0	0	0	0	100		
Cross Area Proficiency		0	0	0	0	0	0	0		